

### **REMARKS**

Entry of this Amendment Under 37 C.F.R. 1.116 is respectfully requested because it cancels a claim and places the application into condition for allowance. Alternately, entry is proper because it places the application into better form for appeal. No new matter is believed to be added to the application by this Amendment.

### **Subject of the Claims**

Claims 2, 4-7 and 10-12 are pending in the application. Claims 11 and 12 have been allowed by the Examiner. Claim 1 is cancelled by this Amendment. The amendments to claims 2 and 7 find support at page 6, lines 17-23 of the specification, as well as in Figures 2A-2C.

### **Interview of the Examiner**

The Applicants thank the Examiner for graciously conducting an interview with the Applicants' representative on April 27, 2004. The Interview Summary has been reviewed and it is believed that it accurately reflects the substance of the interview.

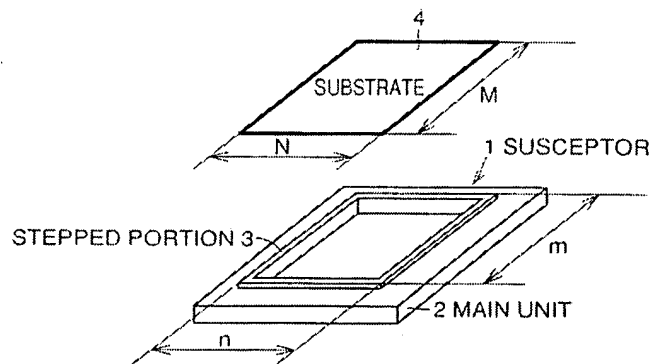
### **Rejections Based Upon Inoue**

Claims 2 and 6 remain rejected under 35 U.S.C. 103(a) as being obvious over Inoue et al. (USP 5,468,344) in view of Hayakawa et al. (USP 5,254,171). The

Examiner adds the teachings of Macdonald et al. (USP 6,494,960) to reject claims 4-10. The Examiner adds the teachings of Gorczyca et al. (USP 6,368,410) to reject claim 5 in combination with Inoue et al. and Hayakawa et al. and to reject claim 7 in view of Inoue et al. Applicants traverse.

The present invention pertains to a susceptor that functions as a novel support for a semiconductor substrate. The inventive susceptor is shown in Fig. 1 of the application, which is reproduced below:

FIG. 1

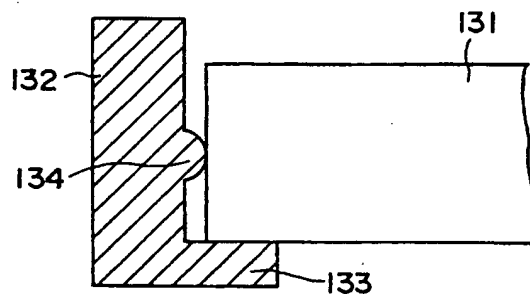


The surface processing using the inventive susceptor finds a typical embodiment in instantly amended claim 2 of the invention, which sets forth:

A surface processing method comprising the steps of:  
masking a portion of a susceptor (1) forming contact with a substrate (4),  
applying a blasting process on said surface of a susceptor (1) that has SiO<sub>2</sub>  
as a main component, and  
etching the surface of said susceptor; and  
wherein said susceptor includes:  
a susceptor main body (2), and

a stepped portion (3) provided on said susceptor main body (2) to support said substrate (4) from the bottom, having a size smaller than said substrate (4), said stepped portion (3) being masked in said masking step, wherein conduction of an end plane of the substrate (4) and the main body (2) can be prevented.

In the Office Action, the Examiner relies upon the clamp of Inoue depicted in Fig. 2, which is reproduced below:



**FIG. 2**

As can be readily observed in Figure 2 of Inoue, Inoue's clamp has a fundamentally different structure and is incapable of performing surface processing, "wherein conduction at an end claim of the substrate (4) and the main body (2) can be prevented." See instantly amended claims 2 and 7. As a result, Inoue clearly fails to be utilizable as the basis of a *prima facie* case of obviousness.

The secondary references of Hayakawa et al., Macdonald et al. and Gorczyca et al. fail to address the deficiencies of Inoue.

As a result, one having ordinary skill would not be motivated by Inoue and any combination of the secondary references to produce the invention as is set forth in independent claims 2 and 7. A *prima facie* case of obviousness has thus

not been made. Claims dependent upon claims 2 and 7 are patentable for at least the above reasons.

These rejections are accordingly overcome and withdrawal thereof is respectfully requested.

**Allowable Subject Matter**

The Examiner has allowed claims 11 and 12.

**Foreign Priority**

The Examiner has acknowledged foreign priority.

**The Drawings**

The Examiner is respectfully requested to indicate whether the drawing figures are acceptable in the next official action.

**Conclusion**

Should there be any outstanding matters that need to be resolved in the present application, the Examiner is respectfully requested to contact Robert E. Goozner, Ph.D. (Reg. No. 42,593) at the telephone number of the undersigned below, to conduct an interview in an effort to expedite prosecution in connection with the present application.

Pursuant to 37 C.F.R. §§ 1.17 and 1.136(a), Applicant(s) respectfully petition(s) for a one (1) month extension of time for filing a reply in connection with the present application, and the required fee of \$110.00 is attached hereto.


If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies, to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fees required under 37 C.F.R. §§ 1.16 or 1.17; particularly, extension of time fees.

Respectfully submitted,

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By 

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Attachment(s)